

ABSTRACT

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The present invention provides a negative
photosensitive resin composition comprising (A) a
5 photocurable resin having a photosensitive group or groups
crosslinkable by light irradiation, (B) a photoacid
generator and (C) a photosensitizer which is a benzopyran
condensed ring compound capable of increasing
photosensitivity to visible light with a wavelength of 480
10 nm or more,
a negative photosensitive dry film prepared by applying
the photosensitive resin composition to a surface of
support film, followed by drying, to form a photosensitive
resin layer, and
15 a method of forming a pattern using the resin composition
or the dry film.